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Abstract of the Disclosure

[0044] A temperature-sensing wafer position detection system and method which uses temperature to determine whether a wafer is properly positioned on a bake plate prior to commencement of a photolithography baking process, for example. The system includes a bake plate and a temperature-sensing apparatus which engages the bake plate and measures the change in temperature (ΔT) of the bake plate over a specified time interval to determine whether the wafer is properly or improperly positioned on the support. In the event that the ΔT of the bake plate is at least as great as a given temperature change threshold value over a specified time interval, this indicates that the wafer is properly positioned for processing.